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09/197521  
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Walter Gomer

9/10/03

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nm	21.	W0 98/49721	11/05/98	PCT	<input checked="" type="checkbox"/>	<input checked="" type="checkbox"/>	
	22.	WO 00/67072	11/09/00	PCT	<input checked="" type="checkbox"/>	<input checked="" type="checkbox"/>	
	23.	EP 0 775 669 A2	05/28/97	EPO	<input checked="" type="checkbox"/>	<input checked="" type="checkbox"/>	
	24.	EP 0 869 516 A1	07/10/98	EPO	<input checked="" type="checkbox"/>	<input checked="" type="checkbox"/>	
	25.	EP 0 869 515 A1	07/10/98	EPO	<input checked="" type="checkbox"/>	<input checked="" type="checkbox"/>	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
	26.	Bae et al., "Imageable Polymers Using Fluorocarbonol Containing Polydienes", <i>Polymer Preprints</i> , 41(2), 1586-1587, (2000).					
	27.	Gabor et al., "Block and Random Copolymer Resists Designed for 193 nm Lithography and Environmentally Friendly Supercritical CO <sub>2</sub> Development", <i>SPIE</i> , 2724, 410-417, (1996).					
	28.	Glaser et al., "Effect of the H <sub>2</sub> O/TEOS Ratio Upon The Preparation and Nitridation of Silica SOL/GEL Films", <i>Journal of Non-Crystalline Solids</i> , 63, 209-221, (1984).					
	29.	Hoggan et al., "Spin Coating and Photolithography Using Liquid and Supercritical Carbon Dioxide", <i>Polymeric Materials and Science Engineering - Fall Meeting</i> , New Orleans, Louisiana, 81, 47-48, (1999).					
	30.	Meerholz et al., "Stability Improvements of High-Performance Photorefractive Polymers Containing Eutectic Mixtures of Electro-optic Chromophores**", <i>Adv. Matr.</i> , 9(13), 1043, (1997).					
	31.	Ober et al., "Imaging Polymers with Supercritical Carbon Dioxide**", <i>Adv. Mater.</i> , 9(13), 1039-1042, (1997).					
	32.	Sundararajan et al., "Supercritical CO <sub>2</sub> Processing for Submicron Imaging of Fluoropolymers", <i>Chem. Mater.</i> , A-H, (1999).					
	33.	Weibel et al., "Patternable Low-K Dielectrics Developed Using Supercritical CO <sub>2</sub> ", <i>Polymer Preprints</i> , 41(2), 1838, (2000).					
af	34.	Yang et al., "Low-Surface-Energy Fluoromethacrylate Block Copolymers with Patternable Elements", <i>Chem. Matr.</i> , 12(1), 33-40, (2000).					
nm	35.	Yu et al., "Microfabrication of Hydrogels as Polymer Scaffolds for Tissue Engineering Applications", <i>Polymer Preprints</i> , 41(2), 1699-1700, (2000).					

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**FORM PTO-1449 U.S. Department of Commerce  
Patent and Trademark Office**
**LIST OF DOCUMENTS CITED BY APPLICANT**

(Use several sheets if necessary)

Attorney Docket Number

5470-316

Serial No.

09/975,211

Applicants: DeSimone et al.

Filing Date: October 10, 2001

Group: 2812

**U. S. PATENT DOCUMENTS**

Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	1.	5,665,527	09/09/97	Allen et al.	430	325	
	2.	6,001,418	12/14/99	DeSimone et al.	427	240	
	3.	6,045,877	04/04/00	Gleason et al.	427	522	
ny	4.	6,165,559	12/26/00	McClain et al.	427	388.1	

**FOREIGN PATENT DOCUMENTS**

		Document Number	Date	Country	Class	Subclass	Translation Yes   No

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

ny	5.	International Search Report for PCT/US01/31504 dated November 30, 2001.					

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